- D(Tz) = duration of exposure of the weakened zone to temperature Tz which leads to blistering

- Tz(t) = temperature at the weakened zone at time t.

~~22. A device for implementing a method according to one of the preceding claims characterized in that it comprises:~~

- ~~A vessel for containing the liquid bath,~~
- ~~Heating means to bring the material of the bath to the liquid state and to hold it thereat.~~

~~23. The device according to the preceding claim characterized in that the heating means comprise lamps and the device comprises means for individual regulating of the power fed to each lamp of the heating means.~~

~~24. The device according to the preceding claim characterized in that the heating means are completed with an additional heating system.~~

~~25. The device according to the preceding claim characterized i n that the additional heating system is a heating system by induction located underneath the vessel.~~

~~26. The device according to one of the three preceding claims characterized in that it comprises~~

- ~~Means for electrically insulating the donor substrate,~~
- ~~Means for measuring capacitance, said means having one electrode to be in contact with the back side of the substrate, and the other electrode to be in contact with the material of the bath,~~
- ~~Means for varying inclination of the surface of the substrate with respect to the surface of the liquid bath.~~

~~27. The device according to the preceding claim characterized in that it further comprises processing means for determining the angle of inclination to be given to the substrate with respect to the surface of the liquid bath.~~

28. The device according to one of the five preceding claims characterized in that it comprises :

- an arm system (41 ),
- a main jack system (42), attached below the arm system,
- a system (43) of "fine" actuators, attached under the main jack system, said system of "fine" actuators carrying the donor substrate,

The arm system allowing bringing rapidly the main jack system and the fine actuators and thus the substrate to above the liquid surface at a well-calibrated distance for example of a few mm,

The main jack system being vertically moveable with respect to said arm system, and allowing, after having been brought above the liquid surface by the arm system, lowering the centre of the donor substrate down to the liquid surface at a programmed rate and with precision,

The system of "fine" actuators allowing the angle of the surface of the donor substrate to be varied and thus allowing an adjustment of the orientation of the substrate with respect to the liquid surface.